## AMENDMENTS TO THE SPECIFICATION
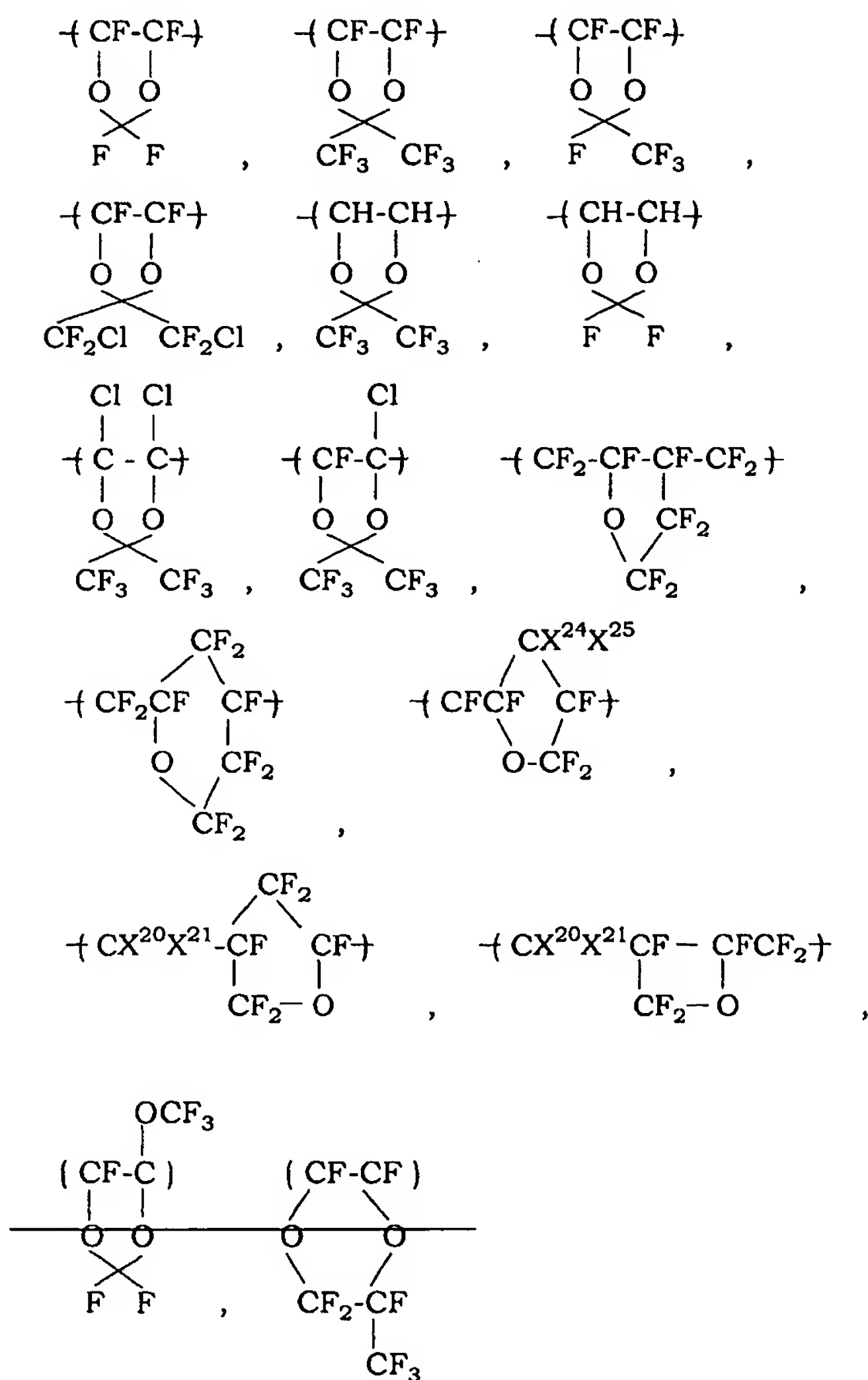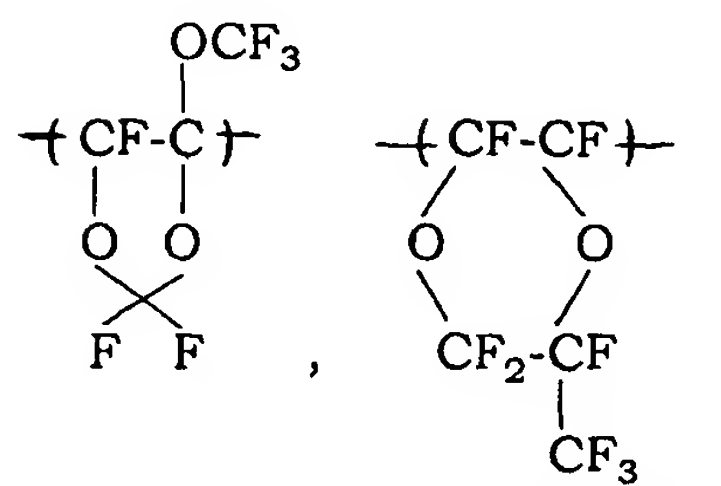
**Please replace the paragraph beginning at line 2 bridging pages 28-29 of the specification with the following amended paragraph:**

Concretely there are:

$$\begin{array}{ccc}
\overset{\displaystyle OCF_3}{\underset{\displaystyle}{|}} & & \\
-\!\!\!\left(\!CF\!-\!\underset{\displaystyle |}{C}\!\right)\!\!\!- & & -\!\!\!\left(\!CF\!-\!CF\!\right)\!\!\!- \\
\underset{\displaystyle \underset{F}{\times}\underset{F}{}}{O\ O} & , & \underset{\displaystyle \underset{|}{CF_2\!-\!CF}}{O\quad O} \\
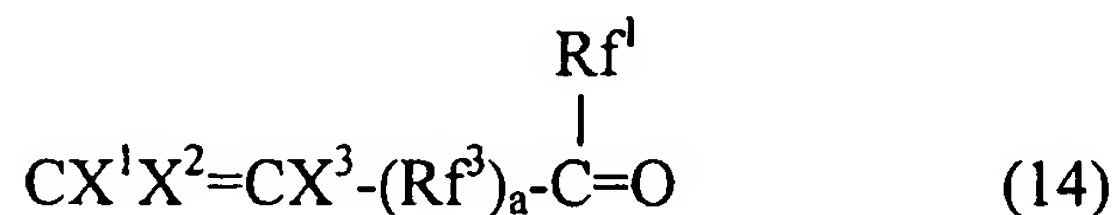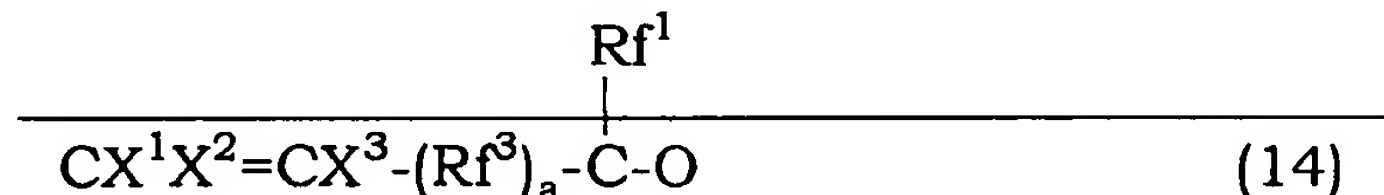& & \underset{\displaystyle CF_3}{}
\end{array}$$

and the like wherein $X^{20}$, $X^{21}$, $X^{24}$ and $X^{25}$ are as defined in the formula (17).

**Please replace the paragraph beginning at line 21 bridging pages 36-37 of the specification with the following amended paragraph:**

The fluorine-containing ethylenic monomer having fluoroalkyl carbonyl group of the present invention is a fluorine-containing monomer represented by the formula (14):
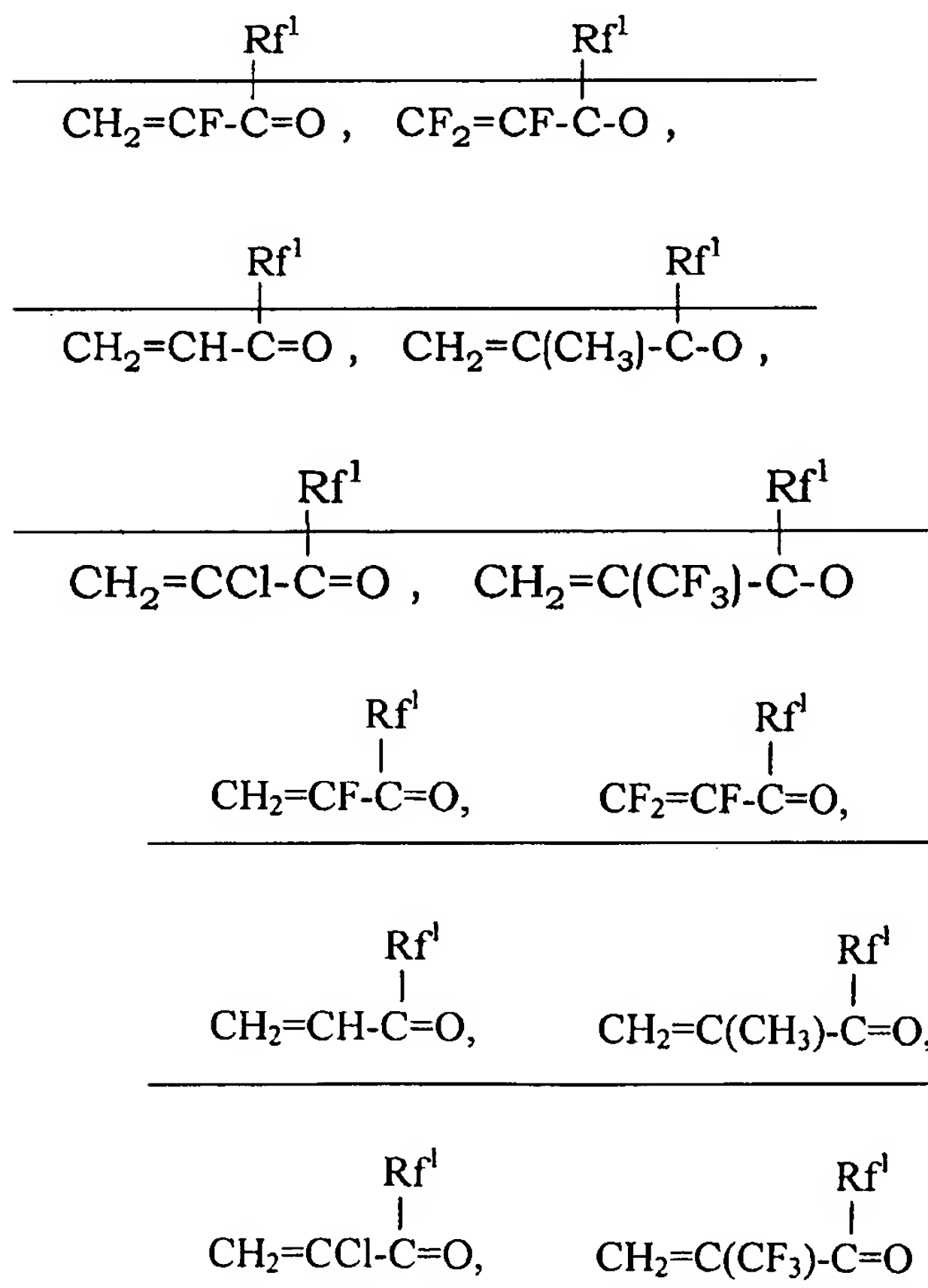
$$CX^1X^2\!=\!CX^3\text{-}(Rf^3)_a\text{-}\overset{\displaystyle Rf^1}{\underset{\displaystyle |}{C}}\text{-}O \qquad\qquad (14)$$

$$CX^1X^2\!=\!CX^3\text{-}(Rf^3)_a\text{-}\overset{\displaystyle Rf^1}{\underset{\displaystyle |}{C}}\!=\!O \qquad\qquad (14)$$

wherein $X^1$ and $X^2$ are the same or different and each is H or F; $X^3$ is H, F, Cl or $CF_3$; $Rf^1$ is a perfluoroalkyl group having 1 to 20 carbon atoms; $Rf^3$ is a fluorine-containing alkylene group having 1 to 40 carbon atoms or a fluorine-containing alkylene group having ether bond which has 1 to 100 carbon atoms and the sum of carbon atom and oxygen atom of two or more; a is 0 or 1.

3

**Please replace the second full paragraph beginning at line 8 at page 38 of the specification with the following amended paragraph:**

When a is 0, the monomer is one represented by the formula (23):

$$CX^1X^2=CX^3-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O \qquad (23)$$

wherein $X^1$ and $X^2$ are the same or different and each is H or F; $X^3$ is H, F, Cl or $CF_3$; $Rf^1$ is as defined in the formula (14). More concretely there are:

$$\frac{CH_2=CF-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O\,,\quad CF_2=CF-\underset{\underset{\displaystyle Rf^1}{|}}{C}-O\,,}{}$$

$$\frac{CH_2=CH-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O\,,\quad CH_2=C(CH_3)-\underset{\underset{\displaystyle Rf^1}{|}}{C}-O\,,}{}$$

$$\frac{CH_2=CCl-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O\,,\quad CH_2=C(CF_3)-\underset{\underset{\displaystyle Rf^1}{|}}{C}-O}{}$$

$$\frac{CH_2=CF-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O,\qquad CF_2=CF-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O,}{}$$

$$\frac{CH_2=CH-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O,\qquad CH_2=C(CH_3)-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O,}{}$$

$$\frac{CH_2=CCl-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O,\qquad CH_2=C(CF_3)-\underset{\underset{\displaystyle Rf^1}{|}}{C}=O}{}$$
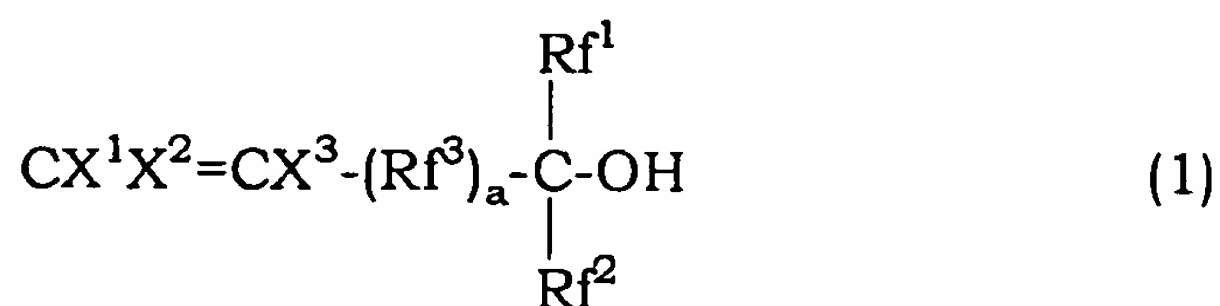
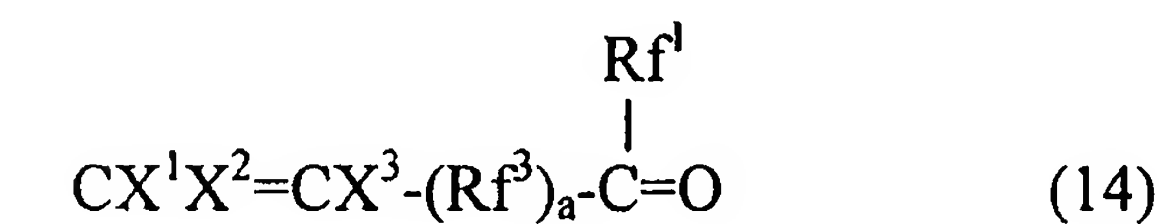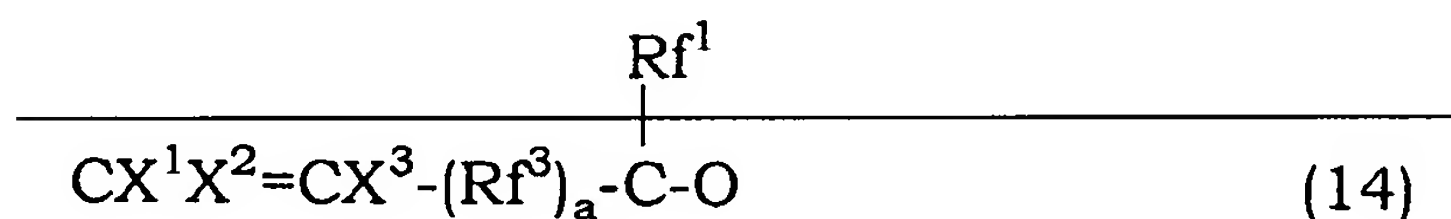and the like, wherein $Rf^1$ is as defined in the formula (14).

**Please delete the present Abstract of the Disclosure.**

**Please add the following new Abstract of the Disclosure:**

There are provided a fluorine-containing ethylenic monomer having hydroxyl group or fluoroalkyl carbonyl group and represented by the formula (1):

$$CX^1X^2{=}CX^3{-}(Rf^3)_a{-}\underset{\underset{Rf^2}{|}}{\overset{\overset{Rf^1}{|}}{C}}{-}OH \qquad (1)$$

and the formula (14):

$$CX^1X^2{=}CX^3{-}(Rf^3)_a{-}\overset{\overset{Rf^1}{|}}{C}{-}O \qquad (14)$$

$$CX^1X^2{=}CX^3{-}(Rf^3)_a{-}\overset{\overset{Rf^1}{|}}{C}{=}O \qquad (14)$$

respectively, wherein $X^1$ and $X^2$ are the same or different and each is H or F; $X^3$ is H, F, Cl or $CF_3$; $Rf^1$ and $Rf^2$ are the same or different and each is a perfluoroalkyl group having 1 to 20 carbon atoms; $Rf^3$ is a fluorine-containing alkylene group having 1 to 40 carbon atoms or a fluorine-containing alkylene group having ether bond which has 1 to 100 carbon atoms and the sum of carbon atom and oxygen atom of two or more; a is 0 or 1, a fluorine-containing polymer having a structural unit of the above-mentioned monomer and a composition for a photoresist. The monomer has good polymerizability, particularly radical polymerizability, and the polymer

obtained by polymerizing the monomer has excellent optical characteristics and is useful as a

base polymer for an antireflection film and for a composition for a resist.